

Japan Micropatterning Committee Meeting Summary and Minutes

SEMI Japan Standards Spring 2013 Meetings
Tuesday, April 9, 2013 15:30-17:30
SEMI Japan, Tokyo, Japan

Next Committee Meeting

SEMI Japan Standards Summer 2013 Meetings
Wednesday, August 28, 2013, 15:30-17:30
SEMI Japan, Tokyo, Japan

Table 1 Meeting Attendees

Co-Chair (Acting): Toshio Suzuki (Dai Nippon Printing)

SEMI Staff: Naoko Tejima (SEMI Japan)

<i>Company</i>	<i>Last</i>	<i>First</i>	<i>Company</i>	<i>Last</i>	<i>First</i>
JEOL	Iida	Mitsuhide	NuFlare Technology	Sakamoto	Shinji
-	Higashikawa	Iwao	Dai Nippon Printing	Suzuki	Toshio
-	Otaki	Masao	SEMI Japan	Tejima	Naoko

** alphabetical order by last name*

Table 2 Leadership Changes

<i>Group</i>	<i>Previous Leader</i>	<i>New Leader</i>
JA Micropatterning Committee Co-chairs	Iwao Higashikawa (Toshiba)	Open

Table 3 Ballot Results

Passed ballots and line items will be submitted to the ISC Audit & Review Subcommittee for procedural review.

Failed ballots and line items were returned to the originating task forces for re-work and re-balloting.

<i>Document #</i>	<i>Document Title</i>	<i>Committee Action</i>
5535	Reapproval of SEMI P35-1106, Terminology for Microlithography Metrology	Passed as balloted
5536	Reapproval of P36-1108, Guide for Magnification Reference for Critical Dimension Measurement for Scanning Electron Microscopes (CD-SEMS)	Passed as balloted

Table 4 Authorized Ballots

<i>Document #</i>	<i>When</i>	<i>SC/TF/WG</i>	<i>Details</i>
5537	The earliest possible cycle	5-year-review Task Force	Line Item Revision to SEMI P23-0200 (Reapproved 1107), Guidelines for Programmed Defect Masks and Benchmark Procedures for Sensitivity Analysis of Mask Defect Inspection Systems

Table 5 Authorized Activities

None

Table 6 New Action Items

<i>Item #</i>	<i>Assigned to</i>	<i>Details</i>
MP120828-1	Mask Data Format for Mask Tools Task Force	To prepare the information (blue) ballot of Doc. 5229, Revision to SEMI P44, as soon as possible.
MP120828-2	5 Year Review Task Force	To draft the document of Doc. 5484, Revision to SEMI P22-0307 to submit it for the earliest possible cycle, 2013.
MP121211-1	5 Year Review Task Force	To draft the document of Doc. 5537, Line Item Revision to SEMI P23-0200 to submit it for the earliest possible cycle, 2013.
MP130409-1	Suzuki Toshio	To try to find a candidate of co-chair in his office
MP130409-2	SEMI staff	To forward adjudication result of Doc.5535 to the ISC A&R Subcommittee for procedural review.
MP130409-3	SEMI staff	To forward adjudication result of Doc.5536 to the ISC A&R Subcommittee for procedural review.

1 Welcome, Reminders and Introductions

Toshio Suzuki, acting committee co-chair, called the meeting to order at 15:30. Self-introductions were made followed by the agenda review.

2 Required Meeting Elements

The meeting reminders on program membership requirement, antitrust issues, intellectual property issues and international effective meeting guidelines, were reviewed by SEMI staff, Naoko Tejima.

3 Leadership Change

Iwao Higashikawa (ex. Toshiba) stepped down as co-chair of Japan Micropatterning Committee. Co-chair is temporarily open as of this committee meeting day. The substitute of co-chairs will be appointed at the next committee meeting.

Action Item: Suzuki Toshio to try to find a candidate of co-chair in his office.

4 Review of Previous Meeting Minutes

The committee reviewed the minutes of the previous meeting held on December 11, 2012.

Motion: To approve the minutes of the previous meeting as written.

By / 2nd: Masako Otaki (-) / Mitsuhide Iida (JEOL)

Discussion: None

Vote: 4 in favor and 0 opposed. **Motion passed.**

Attachment: 01_JA_Micropatterning_Previous_Mtg_Minutes_130409

5 SEMI Staff Report

Naoko Tejima gave the SEMI staff report. This report included SEMI Global 2013 Calendar of Events, NA Standards Spring 2013 Meetings, 2013 Critical Dates for SEMI Standards Ballots, SEMI Standards Publication, ISC Audits & Reviews SC Summary, New Standards Ballot and Membership Systems, New Ballot Formatting Templates, Style Manual and Compilation of Terms, Revised SEMI Regulations & Procedure Guide and Contact Information.

Attachment: 02_SEMI_Staff_Report_130409

6 Liaison Reports

6.1 North America Microlithography Committee Report

Naoko Tejima briefly reported for the North America Microlithography Committee. This report included Task Force and Leadership Changes, Leadership, Current Committees Structure, Meeting Information, Document Review Summary, New Activities, Five-year Review Update and Task Force Updates.

Attachment: 03_NA_Microlithography_Comm_Report_130409

7 Ballot Review

7.1 *Doc.5535, "Reapproval of SEMI P35-1106, Terminology for Microlithography Metrology"* passed committee review as balloted and will be forwarded to the ISC A&R SC for procedural review.

Action Item: SEMI staff to forward adjudication result of Doc.5535 to the ISC A&R Subcommittee for procedural review.

Attachment: 04_Ballot_Report_for_5535_130409

7.2 *Doc.5536, "Reapproval of SEMI P36-1108, Guide for Magnification Reference for Critical Dimension Measurement for Scanning Electron Microscopes (CD-SEMS)"* passed committee review as balloted and will be forwarded to the ISC A&R SC for procedural review.

Action Item: SEMI staff to forward adjudication result of Doc.5536 to the ISC A&R Subcommittee for procedural review.

Attachment: 05_Ballot_Report_for_5536_130409

8 Task Force Reports

8.1 Mask Data Format for Mask Tools Task Force

Toshio Suzuki reported for the Mask data Format for Mask Tools Task Force. Of note:

- Task Force is working for *Doc. 5229, Revision to SEMI P44, Specification for Open Artwork System Interchange Standard (OASIS) Specific to Mask Tools*
- Task Force meeting was held on February 13 and Global Task Force meeting was held on February 22 (Japan Time)
- The Information Ballot will be issued prior to the Letter Ballot issuing

8.2 5 Year Review Task Force

Masao Otaki reported on progress for the 5 Year Review Task Force. Of note:

- *Doc.5535, "Reapproval of SEMI P35-1106, Terminology for Microlithography Metrology", and Doc.5536, "Reapproval of SEMI P36-1108, Guide for Magnification Reference for Critical Dimension Measurement for Scanning Electron Microscopes (CD-SEMS)"* passed committee review as previously discussed.
- TF is drafting the document of *Doc.5484, "Revision to SEMI P22-0307, Guideline for Photomask Defect Classification and Size Definition"* and is planning to submit the letter ballot for the earliest possible cycle, 2013.
- TF is drafting the document of *Doc. 5537, "Line Item Revision to SEMI P23-0200 (Reapproved 1107), Guidelines for Programmed Defect Masks and Benchmark Procedures for Sensitivity Analysis of Mask Defect Inspection Systems"* and is planning to submit the letter ballot for the earliest possible cycle, 2013.

Motion: To submit Doc.#5537 for the earliest possible cycle, 2013

By / 2nd: Masako Otaki (-) / Mitsuhide Iida (JEOL)

Discussion: None.

Vote: 4 in favor and 0 opposed. **Motion passed.**

9 Old Business

9.1 Previous Meeting Action Items

Naoko Tejima reviewed the previous meeting action items.

Table 7 Previous Meeting Actions Items

<i>Item #</i>	<i>Assigned to</i>	<i>Details</i>
MP120828-1	Mask Data Format for Mask Tools Task Force	To prepare the information (blue) ballot of Doc. 5229, Revision to SEMI P44, as soon as possible ... Open
MP120828-2	5 Year Review Task Force	To draft the document of Doc. 5484, Revision to SEMI P22-0307, by January 31 ... Open
MP121211-1	5 Year Review Task Force	To draft the document of Doc. 5537, Line Item Revision to SEMI P23-0200, by the next committee meeting (April 9) ... Open
MP121211-2	SEMI Staff	To send the TF members the Word file of SEMI P23-0200 to draft the Line Item Revision documents ... Closed
MP121211-3	SEMI Staff	To prepare SNARFs and Reapproval ballots of SEMI P35 and P36 for Cycle 1, 2013 ... Closed

10 New Business

None

11 Action Item Review

11.1 New Action Items

Naoko Tejima reviewed the new action items. These can be found in the New Action Items table at the beginning of these minutes.

12 Next Meeting and Adjournment

The next meeting of the Japan Micropatterning Committee is scheduled for Wednesday, August 28, 2013 15:30-17:30, at SEMI Japan, Tokyo, Japan.



Respectfully submitted by:
Naoko Tejima
Manager, Standards
SEMI Japan
Phone: +81.3.3222.5804
Email: ntejima@semi.org

Minutes approved by:

Toshio Suzuki (Dai Nippon Printing), Co-chair (Acting)	May 16, 2013
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Table 8 Index of Available Attachments #1

#	<i>Title</i>
1	JA_Micropatterning_Previous_Mtg_Minutes_130409
2	SEMI_Staff_Report_130409
3	03_NA_Microlithography_Comm_Report_130409
4	Ballot_Report_for_5535_130409
5	Ballot_Report_for_5536_130409

#1 Due to file size and delivery issues, attachments must be downloaded separately. A .zip file containing all attachments for these minutes is available at www.semi.org. For additional information or to obtain individual attachments, please contact Naoko Tejima at the contact information above.